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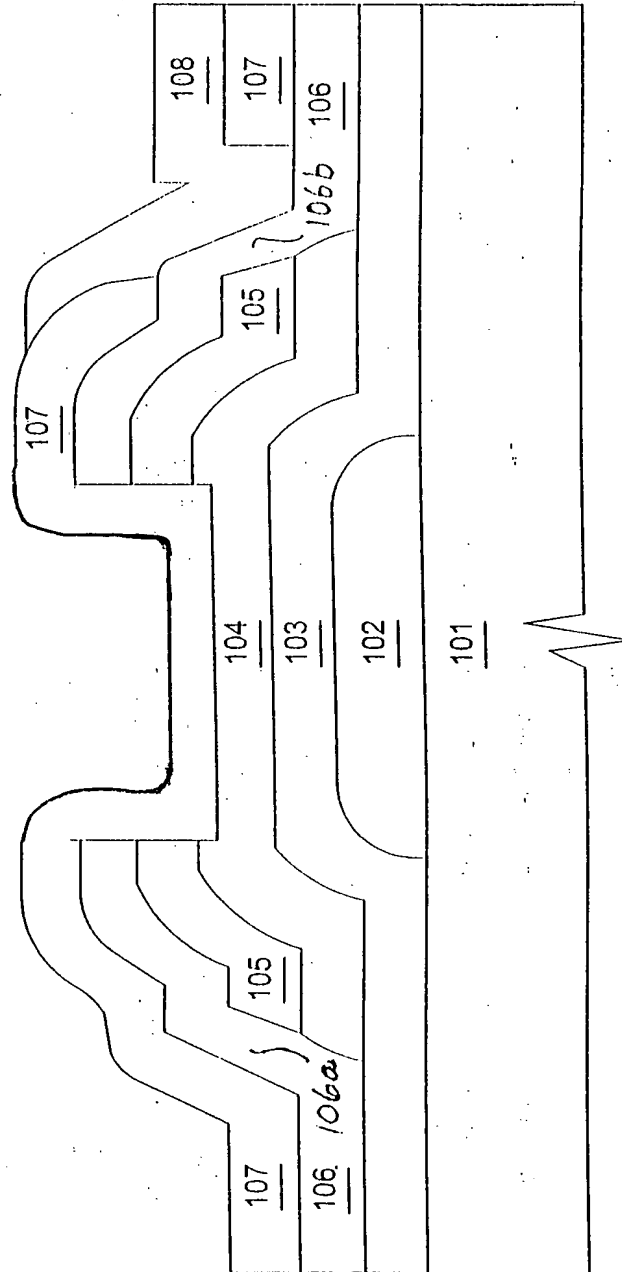


FIG. 1 (Prior Art)

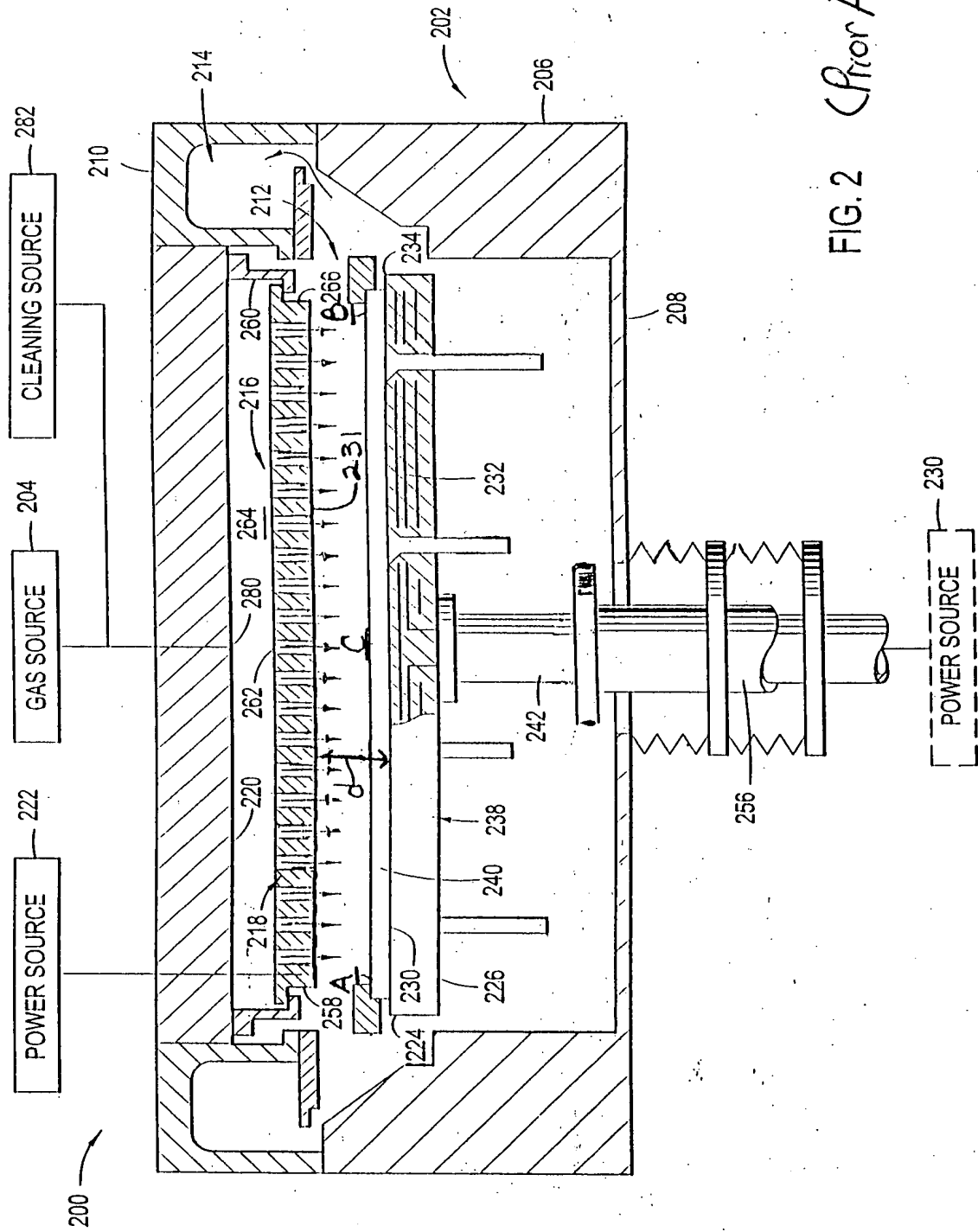


FIG. 2 (Prior Art)

ITO Pattern(MASK5)

ITO Sputtering

Passivation Etch (MASK4)

SiNx PECVD

n+ a-Si Etch-Back

S/D Pattern(MASK3)

S/D Sputtering

a-Si Pattern(MASK2)

n+a-Si/a-Si/SiNx PECVD

Gate Pattern(MASK 1)

Gate Metal Sputtering

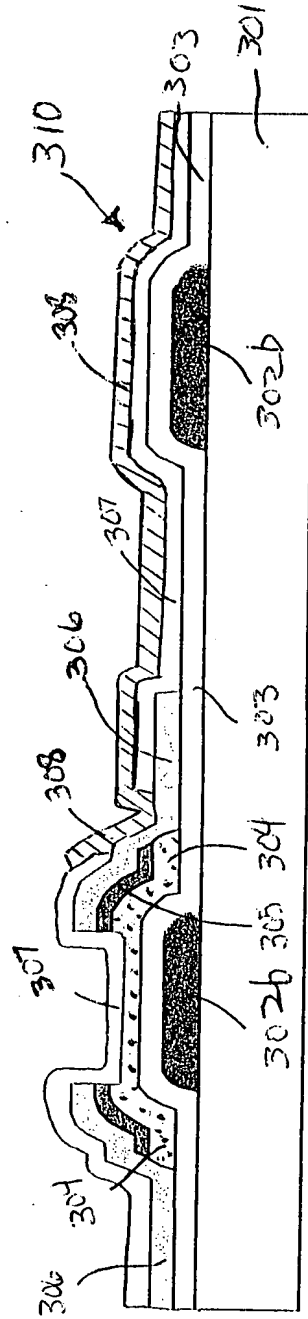
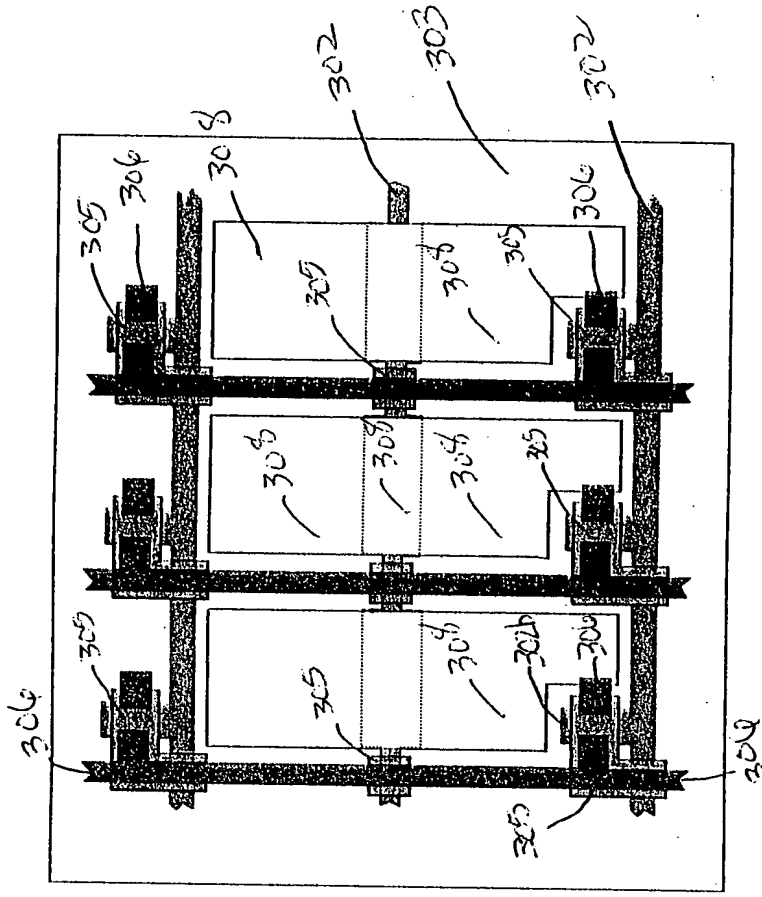


Fig. 3

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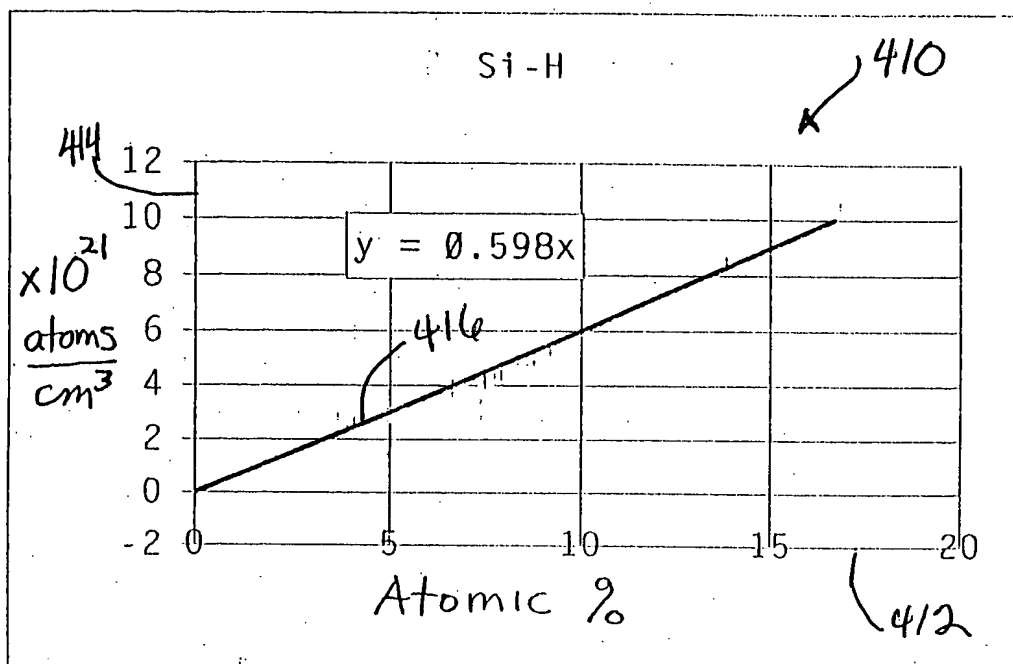


Fig. 4A

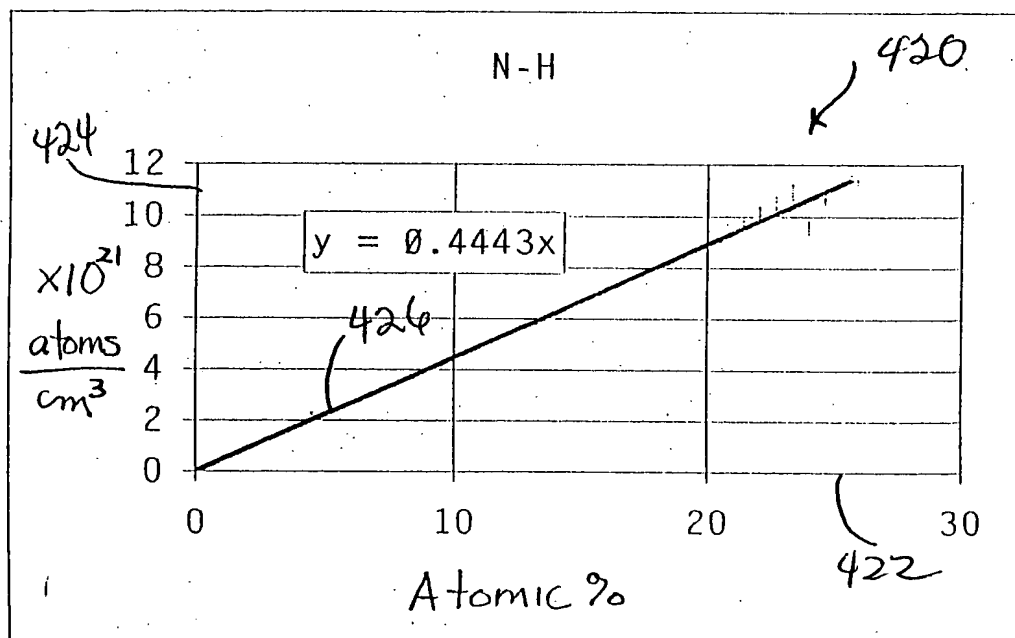


Fig. 4B